Chemicals supplied to NRF Users

**Acids**
- Sulfuric Acid - H2SO4
- BOE 6:1 – NH4F/HF
- Hydrochloric acid - HCL
- Phosphoric acid – H3PO4
- Hydrofluoric acid - HF
- Nitric acid – HNO3
- gold etch
- chrome etch
- Aluminum etch
- iron oxide mask etch
- chrome mask etch

**Bases**
- Ammonium hydroxide – NH4OH
- Hydrogen Peroxide – H2O2

**General Solvents**
- Propanol (Isopropanol)(2-propanol)
- Methanol
- Acetone

**Photolithography**
- Shipley S1813
- AZ9260
- AZ nLOF
- Microchem LOR-A
- Microchem 950PMMA A2
- Microchem 950PMMA A4
- Microchem 950PMMA A6
- MIBK/IPA (1:3)
- PRS 3000
- NMP

**Special Notes about chemicals:**
- Small quantities for pipette dispensing the following photochemicals may be found in the Litho Bay rack, lower shelf.
  - Shipley Microposit S1813
  - AZ 9260
  - nLOF 2035
  - LOR3A
- PMMA is located in the Ebeam Bay solvent bench, lower right door.